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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/666,694	09/18/2003	Ofer Sneh	4551P002D2	1409
8791	7590 06/29/2004	EXAMINER		
	SOKOLOFF TAYLOR &	COLEMAN, WILLIAM D		
12400 WILSHIRE BOULEVARD, SEVENTH FLOOR LOS ANGELES, CA 90025			ART UNIT	PAPER NUMBER
2007111022			2823	
			DATE MAILED: 06/29/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

1		Application No.	Applicant(s)		
Office Action Summary					
		10/666,694	SNEH ET AL.		
	omee Action Cummary	Examin r	Art Unit		
	The MAILING DATE of this communication app	W. David Coleman	2823		
Period fo		ars on the cover sheet with the c	orrespond nee address		
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.  - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.  - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).					
Status					
1)	Responsive to communication(s) filed on 18 Se	eptember 2003.			
	This action is <b>FINAL</b> . 2b)⊠ This action is non-final.				
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.				
Dispositi	Disposition of Claims				
<ul> <li>4) ☐ Claim(s) 73-75 is/are pending in the application.</li> <li>4a) Of the above claim(s) is/are withdrawn from consideration.</li> <li>5) ☐ Claim(s) 74 and 75 is/are allowed.</li> <li>6) ☐ Claim(s) 73 is/are rejected.</li> <li>7) ☐ Claim(s) is/are objected to.</li> <li>8) ☐ Claim(s) are subject to restriction and/or election requirement.</li> </ul>					
Applicati	on Papers				
<ul> <li>9) The specification is objected to by the Examiner.</li> <li>10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.  Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).</li> <li>11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.</li> </ul>					
Priority u	ınder 35 U.S.C. § 119				
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>					
Attachment(s)					
2) Notic 3) Inform	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:			

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### DETAILED ACTION

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claim 73 is rejected under 35 U.S.C. 102(e) as being anticipated by Gates et al., U.S. Patent 6,203,613 B1.

Gates discloses a semiconductor device as claimed. See FIGS. 1A & 1B where Gates discloses the claimed limitations.

Pertaining to claim 73, <u>Gates</u> teaches a structure formed on a substrate comprising: a material layer 14 formed on the substrate 18 in which the material layer is pretreated by introducing a radical specie including any combination of O<sub>2</sub>, H<sub>2</sub>, H<sub>2</sub>O, NH<sub>3</sub>, NF<sub>3</sub>, N<sub>2</sub>, C1 and F to increase AHx (column 4, lines 40-65) termination sites on the surface of the material layer, where x is an integer and A is a non-metal capable of bonding with hydrogen H (see Example 6, where NH<sub>3</sub> is incorporated into the invention, column 10, lines 60-62); a film layer formed above said material layer by repeated introduction of a first precursor followed by a second precursor to deposit said film layer by atomic layer deposition, the first precursor to deposit a first reactive specie on the surface of the material layer, the surface when pretreated being more receptive to have additional bonding with the first reactive specie, due to the increase of AHx termination sites on the surface and the second precursor to deposit a second

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reactive specie to react with the deposited first reactive specie to form said film layer (see Example 5).

### Allowable Subject Matter

Claims 74 and 75 allowed.

The following is an examiner's statement of reasons for allowance: the prior art does not anticipate nor render obviousness as to the further limitation of depositing an insulator layer as claimed on the ALD deposited insulating layer.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

#### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to W. David Coleman whose telephone number is 571-272-1856. The examiner can normally be reached on 9:00 AM-5:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

W. David Coleman Primary Examiner Art Unit 2823

WDC